



Attorney's Docket No. 5649-842

#8/B
2/4/02
PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re: Kang et al.

Serial No.: 09/665,208

Group Art Unit: 2818

Filed: September 18, 2000

Examiner: D. Nhu

For: APPARATUS FOR FORMING THIN FILM

Date: November 21, 2001

Commissioner for Patents
Washington, DC 20231

AMENDMENT

Sir:

This Amendment is responsive to the Office Action (the Action) mailed August 29, 2001. A "Version with Markings to Show Changes Made" can be found at page 11.

In the Claims:

Please cancel Claim 26 without prejudice.

Please replace the following amended claim:

23. (Amended) An apparatus for forming a thin film on a substrate, the apparatus comprising:

a multi-functional chamber configured to deposit a dielectric layer on the substrate;

B1 and

96/17 an oxygen radical or plasma annealing unit connected to the multi-functional chamber and configured to provide oxygen radical or plasma gas to the multi-functional chamber to oxygen radical or plasma anneal one or more electrode and/or dielectric layers on the substrate in the multi-functional chamber, said oxygen radical or plasma annealing unit comprising a gas source selected from the group consisting of O₂, NH₃, Ar, N₂, and N₂O.

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